

10662892

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	19	semiconductor\$2 and optical same tool and gas near flow and (absorptive or absorption or absorb\$3) near (material or substance or layer or film) and photolithograph\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:23
S2	191	semiconductor\$2 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb\$3) near (material or substance or layer or film) and photolithograph\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 12:24
S3	195	semiconductor\$2 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb\$3) near (material or substance or layer or film) and photolithograph\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:19
S4	0	S3 and (optical near tool) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 12:34
S5	25	S3 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/17 12:45
S6	25	(US-20050117134-\$ or US-20040166679-\$ or US-20040086640-\$ or US-20040023419-\$ or US-20040006249-\$ or US-20030113943-\$ or US-20030068834-\$ or US-20030021015-\$ or US-20020142493-\$ or US-20020126268-\$ or US-20020044260-\$ or US-20010038446-\$).did. or (US-6884464-\$ or US-6833949-\$ or US-6759254-\$ or US-6757051-\$ or US-6621557-\$ or US-6563578-\$ or US-6538722-\$ or US-6466365-\$ or US-6411368-\$ or US-5916712-\$ or US-5738959-\$ or US-5679483-\$ or US-5302237-\$).did.	US-PGPUB; USPAT	OR	ON	2005/06/17 12:45

S7	25	S6 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:19
S8	9	"6620630"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 21:59
S9	2	"5108178"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 00:30
S10	32	"5676760"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:45
S11	5	(US-20050117134-\$ or US-20020126268-\$).did. or (US-6757051-\$ or US-6538722-\$ or US-6411368-\$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 15:01
S12	16	"S8" and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 22:35
S13	5	S11 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:10
S14	2	(US-6757051-\$ or US-6411368-\$).did.	USPAT	OR	ON	2005/07/06 22:40
S15	2	S14 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:26

S16	1	S15 and saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:12
S17	0	S9 and saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:12
S18	24	(US-20050117134-\$ or US-20040166679-\$ or US-20040086640-\$ or US-20040023419-\$ or US-20040006249-\$ or US-20030113943-\$ or US-20030068834-\$ or US-20030021015-\$ or US-20020142493-\$ or US-20020126268-\$ or US-20020044260-\$ or US-20010038446-\$).did. or (US-6884464-\$ or US-6833949-\$ or US-6759254-\$ or US-6757051-\$ or US-6621557-\$ or US-6563578-\$ or US-6538722-\$ or US-6466365-\$ or US-6411368-\$ or US-5916712-\$ or US-5738959-\$ or US-5679483-\$ or US-5302237-\$).did.	US-PGPUB; USPAT	OR	ON	2005/07/06 23:12
S19	8	S18 and saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:14
S21	198	semiconductor\$2 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb\$3) near (material or substance or layer or film) and photolithograph\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:15
S22	46	S21 and saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:15

S23	6	S21 and (exceed\$3 or pasted or past or passing or beyond) near2 saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:18
S24	6	semiconductor\$2 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb\$3) near (material or substance or layer or film) and photolithograph\$4 and (exceed\$3 or pasted or past or passing or beyond) near2 saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:19
S25	12	semiconductor\$2 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb\$3) near (material or substance or layer or film) and (exceed\$3 or pasted or past or passing or beyond) near2 saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:29
S26	1	S15 and filter\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:27
S27	14	optical same (tool or system) and gas near flow and (absorptive or absorption or absorb\$3) near3 (material or substance or layer or film) and (exceed\$3 or pasted or past or passing or beyond) near2 saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:16
S28	172649	"438"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:35
S29	8	S28 and optical same (tool or system) and gas near flow and (absorptive or absorption or absorb\$3) same (material or substance or layer or film) and (exceed\$3 or pasted or past or passing or beyond) near2 saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 22:14

S30	10	S10 and saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/06 23:47
S31	0	S9 and saturat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 00:09
S32	1279	gas near flow and (absorptive or absorption) near3 (more or past)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:12
S33	202	S32 and semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 15:08
S34	8	(US-20030113943-\$ or US-20030068834-\$ or US-20040166679-\$ or US-20040023419-\$).did. or (US-5567630-\$ or US-6759254-\$ or US-6620630-\$ or US-5646050-\$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 10:16
S35	8	S34 and saturation	US-PGPUB; USPAT	OR	ON	2005/07/07 10:16
S36	2	(US-6757051-\$ or US-6411368-\$). did.	USPAT	OR	ON	2005/07/07 12:12
S37	2	S36 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 17:21
S38	0	S37 and gas near flow and (absorptive or absorption) near3 (more or past)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:12

S39	2	S37 and gas near flow and (absorptive or absorption)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:12
S40	1738	optical same (tool or system) and gas near flow and (absorptive or absorption or absorb\$3) near3 (material or substance or layer or film)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:18
S41	110	S40 and (gas near flow) same ((absorptive or absorption or absorb\$3) near3 (material or substance or layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:19
S42	50	S40 and (gas near flow) same ((absorptive or absorption or absorb\$3) near3 material)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:36
S43	308	S40 and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:30
S44	16	S42 and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 16:52
S45	10	S42 and ((absorptive or absorption or absorb\$3) near3 material) same glass	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:22
S46	3	(US-20010028992-\$).did. or (US-4913260-\$ or US-6629375-\$). did.	US-PGPUB; USPAT	OR	ON	2005/07/07 12:30

S47	24	(US-20050117134-\$ or US-20040166679-\$ or US-20040086640-\$ or US-20040023419-\$ or US-20040006249-\$ or US-20030113943-\$ or US-20030068834-\$ or US-20030021015-\$ or US-20020142493-\$ or US-20020126268-\$ or US-20020044260-\$ or US-20010038446-\$).did. or (US-6884464-\$ or US-6833949-\$ or US-6759254-\$ or US-6757051-\$ or US-6621557-\$ or US-6563578-\$ or US-6538722-\$ or US-6466365-\$ or US-6411368-\$ or US-5916712-\$ or US-5738959-\$ or US-5679483-\$ or US-5302237-\$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 12:38
S48	24	S47 and (optical same(tool or system)) same (gas near flow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:21
S49	0	S48 and photolithograph\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:25
S50	24	S48 and photolithograph\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 12:39
S51	8759	"I7" and (absorptive or absorption or absorb\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:20
S52	24	S48 and (absorptive or absorption or absorb\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:20

S53	15	optical same tool and gas near flow and (absorptive or absorption or absorb\$3) near material and photolithograph\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:17
S54	132065	"250"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 13:27
S55	175	S54 and gas near flow and (absorptive or absorption or absorb\$3) near material	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:03
S56	20	S54 and gas near flow same (absorptive or absorption or absorb\$3) near material	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:07
S57	0	"230"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:07
S58	91611	"356"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:17
S59	2	S58 and optical same tool and gas near flow and (absorptive or absorption or absorb\$3) near material and photolithograph\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:19
S60	5	S58 and optical same tool and gas near flow and (absorptive or absorption or absorb\$3) near material	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:19

S61	0	S41 and photolithograph\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:25
S62	24	S41 and photolithograph\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 14:25
S63	11	S47 and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 15:16
S64	3	(US-6757051-\$ or US-6538722-\$ or US-6411368-\$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 15:01
S65	4	(US-5108178-\$ or US-5686996-\$ or US-6411368-\$ or US-6757051-\$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 15:02
S66	5	(US-5108178-\$ or US-5686996-\$ or US-6411368-\$ or US-6757051-\$ or US-5676760-\$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 16:30
S67	1	S66 and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 15:10
S68	31	S55 and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 15:29
S69	195	((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon) same gas near flow	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:57
S70	22	((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon) same gas near flow same (bead\$2 or sphere\$2 or blob\$2 or bubble\$2 or ball\$2 or orb\$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 23:32

S71	16	((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon) same gas near flow same (bead\$2 or sphere\$2 or blob\$2 or ball\$2 or orb\$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 16:17
S72	5	(US-6491885-\$ or US-4002722-\$). did. or (US-3486298-\$ or US-3339350-\$ or US-3263400-\$). did.	USPAT; USOCR	OR	ON	2005/07/07 16:26
S73	7	(US-5108178-\$ or US-5686996-\$ or US-6411368-\$ or US-6757051-\$ or US-5676760-\$ or US-4002722-\$ or US-6491885-\$).did.	US-PGPUB; USPAT	OR	ON	2005/07/07 22:30
S74	2	S73 and gas near flow and optical near (system or tool)	US-PGPUB; USPAT	OR	ON	2005/07/07 16:39
S75	2	S74 and (absorption or absorb or absorptive or adsorption or adsorb or adsorptive)	US-PGPUB; USPAT	OR	ON	2005/07/07 16:39
S76	2	S73 and (gas near flow) same (optical near (system or tool))	US-PGPUB; USPAT	OR	ON	2005/07/07 16:43
S77	2	S76 and (absorption or absorb or absorptive or adsorption or adsorb or adsorptive)	US-PGPUB; USPAT	OR	ON	2005/07/07 17:19
S78	2	S77 and gas near flow	US-PGPUB; USPAT	OR	ON	2005/07/07 16:43
S79	6	S73 and gas near flow	US-PGPUB; USPAT	OR	ON	2005/07/07 17:05
S80	2	S75 and (absorption or absorb or absorptive or adsorption or adsorb or adsorptive)	US-PGPUB; USPAT	OR	ON	2005/07/07 17:19
S81	63	(optical same(tool or system)) same (gas near flow) and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 18:38
S82	7	S73 and gas\$3	US-PGPUB; USPAT	OR	ON	2005/07/07 17:39
S83	4	S73 and gas\$3 same (filter\$3 or purg\$4)	US-PGPUB; USPAT	OR	ON	2005/07/07 17:48
S84	5	S73 and gas\$3 same (filter\$3 or purg\$4 or absorption or absorb or absorptive or adsorption or adsorb or adsorptive)	US-PGPUB; USPAT	OR	ON	2005/07/07 18:04
S85	2	S84 and (tubular or tub\$3)	US-PGPUB; USPAT	OR	ON	2005/07/07 18:57
S86	1	S85 and (reflect\$4 or refract\$4 or deflect\$4)	US-PGPUB; USPAT	OR	ON	2005/07/07 18:26

S87	12	S81 and photolithograph\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 18:41
S88	10	S87 and contaminat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 18:42
S89	5	S73 and contaminat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 19:05
S90	3	S73 and contaminat\$4 and photolithograph\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 18:43
S91	1	S85 and optical\$4	US-PGPUB; USPAT	OR	ON	2005/07/07 18:57
S92	4	S89 and (light\$2 or optical\$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 22:15
S93	4	(US-6757051-\$ or US-6411368-\$ or US-5686996-\$ or US-5108178-\$).did.	USPAT	OR	ON	2005/07/08 00:23
S94	2	S93 and vacuum\$2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 22:15
S95	642128	S93 regula\$4	USPAT	OR	ON	2005/07/07 22:16
S96	3	S93 and regula\$4	USPAT	OR	ON	2005/07/07 22:29
S97	2	S93 and polymer\$3	USPAT	OR	ON	2005/07/07 23:01
S99	3	S93 and (oxygen or water)	USPAT	OR	ON	2005/07/07 23:04
S10 0	3	S93 and (oxygen or water or liquid\$2)	USPAT	OR	ON	2005/07/07 23:04
S10 1	2	(US-4002722-\$ or US-6491885-\$). did.	USPAT	OR	ON	2005/07/07 23:31

S10 2	2	S101 and glass	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/07 23:31
S10 3	2	S102 and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon) same gas near flow same (bead\$2 or sphere\$2 or blob\$2 or bubble\$2 or ball\$2 or orb\$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:19
S10 4	0	S103 and (semiconductor\$2 or wafer\$2 or photolithograph\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:20
S10 5	3	S93 and (semiconductor\$2 or wafer\$2 or photolithograph\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:23
S10 6	5	(US-6757051-\$ or US-6411368-\$ or US-5686996-\$ or US-5108178-\$ or US-5676760-\$).did.	USPAT	OR	ON	2005/07/08 00:23
S10 7	4	S106 and (semiconductor\$2 or wafer\$2 or photolithograph\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:25
S10 8	1	S107 and atomic near absorption	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:27
S10 9	1	S107 and atomic near absorption and gas\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:35
S11 0	1	S107 and atomic near absorption and gas\$3 and photolithograph\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:36

S11 1	1	(US-5676760-\$).did.	USPAT	OR	ON	2005/07/08 00:36
S11 2	1	S111 and atomic near absorption and gas\$3 and photolithograph\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:54
S11 3	16294	438/7,14,16,102,115,101,166,22,365,482,487,509,513,540,57,597,603,618,635,680,783,784,795.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 00:55
S11 4	0	S113 and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon) same gas near flow and (optical same(tool or system)) same (gas near flow) and (semiconductor\$2 or wafer\$2 or photolithograph\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:02
S11 5	7278	250/305,338,339,306,440.11,441.11,442.11,443,345,373,504,336.1,338.5,339.04,370.01,374.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:02
S11 6	0	S115 and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon) same gas near flow and (optical same(tool or system)) same (gas near flow) and (semiconductor\$2 or wafer\$2 or photolithograph\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:03
S11 7	9801	257/66,629,687,700,713,78-80,99.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:03
S11 8	0	S117 and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon) same gas near flow and (optical same(tool or system)) same (gas near flow) and (semiconductor\$2 or wafer\$2 or photolithograph\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:04

S11 9	4201	356/246,432,437,499.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:04
S12 0	0	S119 and ((absorptive or absorption or absorb\$3) near3 material) same (glass or polymer\$2 or silicon) same gas near flow and (optical same(tool or system)) same (gas near flow) and (semiconductor\$2 or wafer\$2 or photolithograph\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 01:04